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ABBREVIATIONS AND SYMBOLS

E_A Activation energy

K Adsorption equilibrium constant

A Band bending depth

E_e Bandgap energy

T_{bp} Boiling point

k_B Boltzmann constant

 H_{CHEM} Chemical energy

 β Collision frequency

C Concentration

 C_t Concentration as a function of temperature

E_C Conduction band edge

R² Correlation coefficient value

 d_{XRD} , d_{hkl} Crystallite size from XRD

 L_{D} Debye length

T_{d/mp} Decomposition/melting point

Density of sites covered by adsorbate

Density of surface adsorption sites

D_a Diameter

D Diffusion coefficient

E_D	Dissociation energy
r_c	Distance of chemical bond on surface
n_d	Donor concentration
$n_{\it eff}$	Effective density of states
e ⁻	Electron
χ	Electron affinity
e	Electron charge
m_e	Electron effective mass
Θ	Equilibrium coverage
E_F	Fermi level
$\boldsymbol{\theta}$	Fractional coverage
υ	Frequency of light
a_s	Fused sphere surface area
τ	Grain boundary diffusion
$D_b(T)$	Grain boundary diffusion coefficient as a
	function of temperature
w_b	Grain boundary width
$h^{\scriptscriptstyle +}$	Hole
m_h	Hole effective mass
ight by	Ionization potential
righ	t s ^{Length} reserved
\boldsymbol{A}	Light absorption coefficient

$E_{\scriptscriptstyle U}$	Localized states
В	Magnetic flux densities
Ω	Molar volume of diffusing species
N_i	Net impurity concentration
N	Number concentration of particles
N_d	Number of dopant donor atoms
$p_{ m gas}$	Partial pressure of gas
θ	Peak position
$oldsymbol{eta}_k$	Peak width at half maximum intensity
l	Penetration depth of light into solid
$arepsilon_0$	Permittivity of free space
$oldsymbol{arepsilon}_S$	Permittivity of semiconductor
H_{PHY}	Physical energy
h	Planck's constant
P	Pressure
$d_{\scriptscriptstyle BET}$	Primary particle size from BET
r	Radius
k	Rate constants
	Reaction rate
g ht C	Sensor conductance
R	Sensor resistance
k_{s}	Shape factor

c	Speed of light
$G \sim 90$	Standard Gibbs energy
ε	Static dielectric constant
а	Surface area
$ heta_{\scriptscriptstyle S}$	Surface coverage
V_s	Surface potential
$eV_{\it surface}$	Surface potential barrier
l'w	Surface space charge layer
E_{s}	Surface state energy level
$N_{\scriptscriptstyle S}$	Surface state density
r	Surface tension
T	Temperature
W	Thickness of space-charge layer
$ au_{tr}$	Transit time of photogenerated charges
E_t	Trap energy
λ	Wavelength of light
ρ	Weighted density
ALS UM 9	Acceptor-related
ARPES	Angle-resolved photoelectron spectroscopy
APs	Antiphase boundaries

AFM Atomic force microscope

Basal plane

BP

Basal plane

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BET Brunauer Emmett and Teller

CVD Chemical vapor deposition

CB Conduction band

TCO Conductive transparent oxide

DRS Diffuse reflectance spectroscopy

DL Donor-related

EPMA Electron probe microanalysis

EDS, EDX Energy dispersive spectroscopy

FET Field effect transistors

FESEM Field emission scanning electron microscopy

FASP Flame-assisted spray pyrolysis

FSP Flame spray pyrolysis

FWHM Full width at half maximum

HREM High resolution electron microscopy

ITO Indium tin oxide

ICP-OES Inductively coupled plasma optical emission

spectroscopy

IBs Inversion boundaries

JCPDS Joint Committee on Powder Diffraction

Standards

LD Laser diodes

LED Light emitting diodes

MO Methyl orange

MB Methylene Blue

MBE Molecular beam epitaxy

NBs Nanobelts

NSs Nanostructures

NBE Near-band-edge

OECD Organisation for Economic Co-operation and

Development

PES Photoelectron spectroscopy

PL Photoluminescence

pgms Platinum group metals

POQ_{hkl} Preferred orientation

PLD Pulse laser deposition

RPP Rapid photothermal processing

RHEED Reflection high-energy electron diffraction

RMS Root mean square

SAED Selected area electron diffraction

SZO Sn-doped ZnO

SSA Specific surface area

SILAR Successive ionic layer adsorption and reaction

TEM Transmission electron microscopy

TFT or TTFT (Transparent) thin film transitions

TSCD Two-stage chemical deposition

UAs Unsaturated alcohols

USP Ultrasonic spray pyrolysis

UV-vis Ultraviolet-visible

VB Valence band

VFS Vapor-fed flame synthesis

VLS Vapor-liquid-solid

XRD X-ray diffraction

XPS X-ray photoelectron spectroscopy

